Notice of References Cited Application/Control No. | Applicant(s)/Patent Under Reexamination SHI ET AL. | Examiner | Art Unit | Toan M. Le | 2863 | Page 1 of 1

U.S. PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	Α	US-6,915,232	07-2005	Kitajima et al.	702/171
	В	US-5,498,974	03-1996	Verkuil et al.	324/767
	С	US-			,
	D	US-			
	Ε	US-			
	F	US-			
	G	US-			
	н	US-		·	
	-	US-			
	J	US-			
	К	US-		·	
	L	US-			
	М	US-			

FOREIGN PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	N					
	0			·		
	Р					
	Q					
	R					
	s					·
	Т					

NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)				
	U	Hung et al., Metrology Study of Sub 20 Angstrom Oxynitride by Corona-Oxide-Silicon (COS) and Conventional C-V Approaches, 2002, Mat. Res. Soc. Symp. Proc., Vol. 716, pages 119-124				
	v					
	w					
	х					

*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).) Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.